

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION
(PTO-1449)



ATTY. DOCKET NO.
005920
USA/FPS/MMCS/APC

SERIAL NO.
09/943,383

APPLICANT
SHANMUGASUNDRAM et al.

FILING DATE
August 31, 2001

GROUP
2823

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	5,901,313	05/04/99	Wolf et al.			09/02/97
	6,002,989	12/14/99	Shiba et al.			04/01/97
	6,094,688	07/25/00	Mellen-Garnett et al.			03/12/98
	6,340,602	01/22/02	Johnson et al.			02/12/01
	6,345,288	02/05/02	Reed et al.			05/15/00
	6,368,879	04/09/02	Toprac			09/22/99
	US-2002/0107604	08/08/02	Riley et al.			12/06/00
	6,470,230	10/22/02	Toprac et al.			01/04/00
	6,482,660	11/19/02	Conchieri et al.			03/19/01
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						Yes	No
	WO 99/59200	11/18/99	WIPO			X	
	WO 01/52319	07/19/01	WIPO			X	

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	Williams, Randy, Dadi Gudmundsson, Kevin Monahan, Raman Nurani, Meryl Stoller and J. George Shanthikumar. October 1999. "Optimized Sample Planning for Wafer Defect Inspection," <i>Semiconductor Manufacturing Conference Proceedings, 1999 IEEE International Symposium on Santa Clara, CA</i> . Piscataway, NJ. pp. 43 - 46.
	23 July 2003. Invitation to Pay Additional Fees and Communication Relating to the Results of the Partial International Search for PCT/US02/19116.
	01 August 2003. Written Opinion for PCT/US01/27406.
	20 August 2003. Written Opinion for PCT/US01/22833.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
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	5,347,446	09/13/94	Iino et al.			02/10/92	
	5,519,605	05/21/96	Cawfield			10/24/94	
	6,128,016	10/03/00	Coelho et al.			12/20/96	
	6,219,711	04/17/01	Chari			10/01/97	
	6,249,712	06/19/01	Boiquaye			09/25/96	
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						Yes	No
	EP 1 067 757	01/10/01	Europe			X	
	WO 01/33277	05/10/01	WO			X	
	WO 02/31613 A2	04/18/02	WO			X	
	WO 02/31613 A3	04/18/02	WO			X	
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	Levine, Martin D. 1985. <i>Vision in Man and Machine</i> . New York: McGraw-Hill, Inc. pp. ix-xii, 1-58.						
	Pilu, Maurizio. September 2001. "Undoing Page Curl Distortion Using Applicable Surfaces." <i>IEEE International Conference on Image Processing</i> . Thessalonica, Greece.						
	23 May 2003. Written Opinion for PCT/US01/24910.						
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SHEET 1 OF 2

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	5,427,878	06/27/95	Corliss			05/16/94
	5,534,289	07/09/96	Bilder et al.			01/03/95
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						Yes	No
	WO 01/11679	02/15/01	WIPO			X	
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	Miller, G. L., D. A. H. Robinson, and J. D. Wiley. July 1976. "Contactless measurement of semiconductor conductivity by radio frequency-free-carrier power absorption." <i>Rev. Sci. Instrum.</i> , Volume 47, No. 7. pp. 799 - 805.
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	El Chemali, Chadi et al. July/August 2000. "Multizone uniformity control of a chemical mechanical polishing process utilizing a pre- and postmeasurement strategy." <i>J. Vac. Sci. Technol.</i> Volume 18, No. 4. pp. 1287 - 1296.						
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	"3D optical profilometer MicroXAM by ADE Phase Shift." http://www.phase-shift.com/microxam.shtml .						
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